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(2013 / 1/ 28 2012/ 11 / 20 الملخص (ZnO) 400°C (CVD) (ZnO) Cs^{137} (0, 0.5, 1, 2) Gy .(2, 4, 8, 10) hours (320-1000) nm 85% 63.4% 1000 nm 0.5 Gy 990 nm 4h 46.79% eV(1.92, 2.3, 1.5, 1.7) eV (2.51, 2.6, 2.5)3.25 eV $.0.236 \text{ x} 10^{-3} \Omega.\text{cm}$ $(8.79-12.56) \times 10^3 \Omega$.cm

The Study of the Effect of Gamma Rays and Neutrons on the Physical Properties of Zinc Oxide Thin Film

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ABSTRACT

In this paper, Zinc Oxide (ZnO) thin films were prepared by Chemical Vapor Deposition technique (CVD), at a normal atmospheric pressure on a glass substrate at temperature 400° C. The structural, optical and electrical properties of the films were studied before and after gamma-ray irradiation, with different radiation doses (0, 0.5, 1, 2) Gy. Also, other samples were exposed to neutrons beam for exposure periods (2,4,8,10) hours. The transmittance spectrum was measured as a function of wavelength in the range (320-1000) nm. The highest transmittance of the prepared films was 85%, thus decreased after gamma-ray irradiation to 63.4% at dose 0.5Gy and wavelength 1000 nm, but when irradiated by neutrons beam has decreased to 46.79% at time of radiation 4h and wavelength 990 nm. The energy gap of the prepared films was (3.25) eV where those radiated, were (2.51, 2.6, 2.5) eV for given gamma-ray dose and (1.92, 2.3, 1.5, 1.7) eV for neutron beam, for given exposure time respectively. The expected Change due to the change in the nature of material after radiation. The measured electrical resistivity of irradiated films was found to be $(8.79-12.56) \times 10^3 \Omega$.cm where it was $0.236 \times 10^{-3} \Omega$.cm before the irradiation.

Keywords: ZnO thin film, gamma-rays, neutron flux.

	ZnO			
(3.2 eV)		60 meV		
	II-VI		.(Gür et al., 2008)	
			.(Bin Mahmud, 2008)	
			.(Gür <i>et al.</i> , 2008)	
.(Ian steward, 2010)			
			ZnO	
(yun et al.,	2012)			
			.(ILican et al., 2008)	

```
(ZnO)
                                                                          .(Arshak et al., 2005)
          (Myoung et al., 2002)
                                                                      (Hu et al., 2001)
                                       (Yang et al., 2010) (sol-gel method)
                                                                        (Kathirvel et al., 2009)
                .(Purica et al., 2002)
                                                                         .ZnO
                                        (ZnO)
                                                                                         (CVD)
                                                                        400°C
            (Zn(CH_3CO_2)_2.2H_2O)
                            /sumy state university)
                                                                         .98%
                                                                              Cs^{137}
                0.132 Ci
                                           662 keV
                                                 (0, 0.5, 1, 2) Gy
                                                                                        (6Gy/h)
(5,10,20) min
                                                                     8mm
                                    (1×10<sup>14</sup>neutrons/cm<sup>2</sup>)
                                                                               (Model 88-1H)
                                                                   (1.966\times10^8 \text{ neutrons/cm}^2.\text{s})
                           (2, 4, 8, 10) h
                              ZnO
                                                                                           5<sub>m</sub>m
Scanning Electron )
                                                                                  (XRD)
(Spectrophotometer)
                                                                                   (Microscopy
                                                    (320 - 1000) nm
                                                                          .ZnO
                                                             (XRD)
                                                                           (1)
Gy
                                                              (1a)
                                                                                   (0, 0.5, 1, 2)
                            (201) (112) (200) (103) (110) (102) (101) (002) (100)
```

$$D = \frac{0.9 \,\lambda}{B \cos \theta_{\scriptscriptstyle R}} \tag{1}$$

:

10000 dre 7500 dre 2500 dre 25

.....

ZnO (XRD) (1)

ZnO XRD :1

Data from fig (4-1)							Data from	
a=3.26 Å								Jcpds card
c=5.26 A								a=3.249 A
C 5.20 11							c=5.205 Å	
Peak	111	d	2θ	D(nm)	D(nm)	D(nm)	D(nm)	d
No.	hkl	(A)	(deg)	0 rad	50 rad	100 rad	200 rad	(Å)
1	100	2.84	31.5	92.4	99.78	100.14	-	2.816
2	002	2.63	34	95.62	96.92	101.9	-	2.602
3	101	2.46	36.5	97.6	99.85	101.16	98.29	2.476
4	102	1.92	47.5	100.07	107.44	109.13	-	1.911
5	110	1.64	56.3	100.4	108.28	114.5	-	1.626
6	103	1.47	63	99	103.82	104.21	-	1.477
8	112	1.37	68	105	110.88	116.47	_	1.379

(1)

200 rad

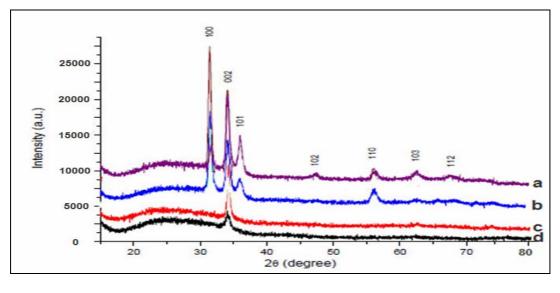
.(101)

ZnO (2)

(2, 4, 8,10) h

.(101) (002) (100)

(002)



.

ZnO XRD :2

	Data from fig (2) a=3.26 Å c=5.26 Å					Data from Jcpds card a=3.249 Å c=5.205 Å			
Peak No.	hkl	d o (A)	20 (deg)	D(nm) 0 hours	D(nm) 2 hours	D(nm) 4 hours	D(nm) 8 hours	D(nm) 10 hours	d (Å)
1	100	2.83	31.6	91.97	91.95	103.51	-	-	2.816
2	002	2.62	34.1	95.13	88.84	98.29	103.66	87.16	2.602
3	101	2.46	36.5	89.22	70	72.56	-	-	2.476
4	102	1.90	47.6	87.02	87.16	-	-	-	1.911
5	110	1.63	56.3	98.19	90.17	69.64	-	-	1.626
6	103	1.47	63	74.74	77.86	-	-	-	1.477

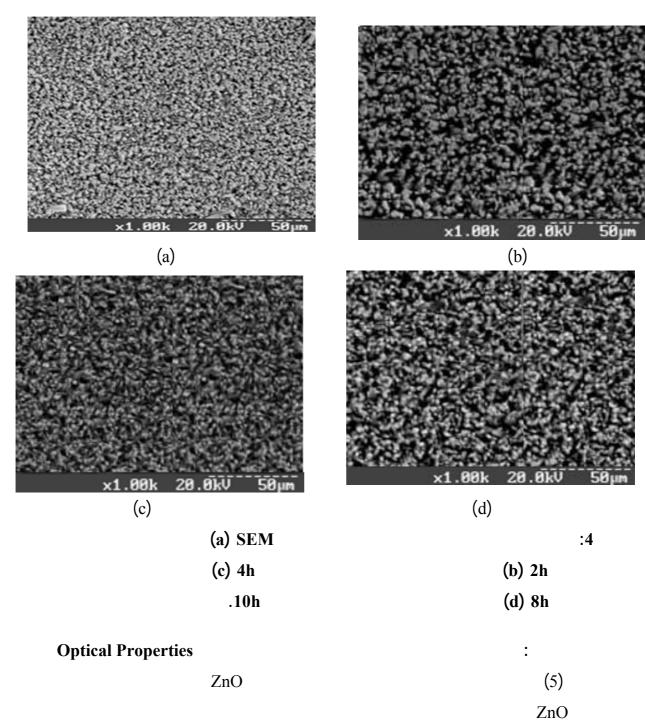
(2) (102) (002) (100)

..... (110) (002) .(002) (8,10) h **Scanning Electron Microscopy** (3a) (3) (0.5, 1, 2) Gy .(3 b, c, d) x1.00k 20.0kV (a) (b) x1.00k (d) (c) SEM :3

(c) 0.5 Gy

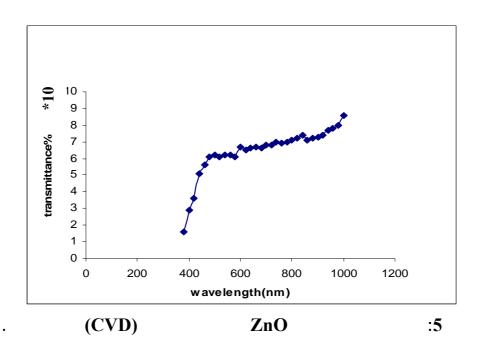
(b) (a) .2 Gy (d) 1 Gy

.

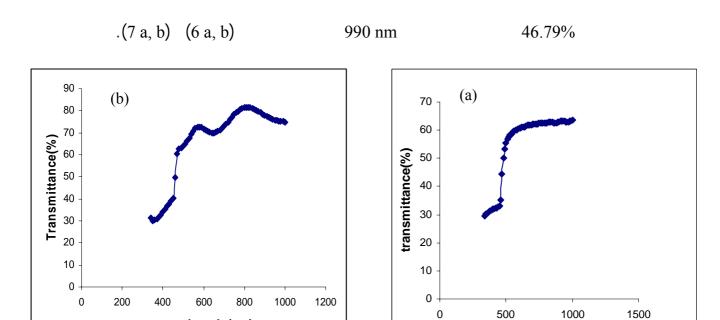


ZnO

93

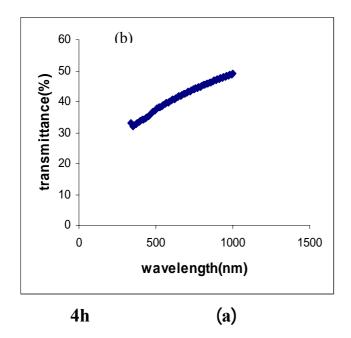


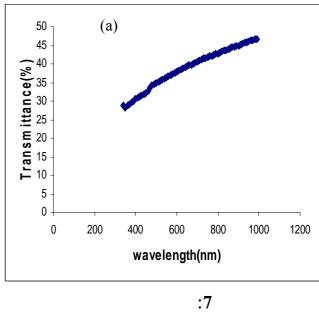
(50,100) rad 200 rad 63.4%



(b) 0.5 Gy (a) wavelength(nm) :6

wavwlength (nm)





(b)

(9 a, b) (8 a, b) :(Heavens, 1965) (ZnO)

.10h

 α = 2.303 (A-A')/t(4.3)

•

:(A-A')

: t

:α

 $\alpha h v = A(h v - E_g)^r \dots (4.4)$

:

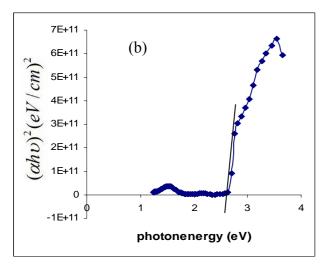
: A

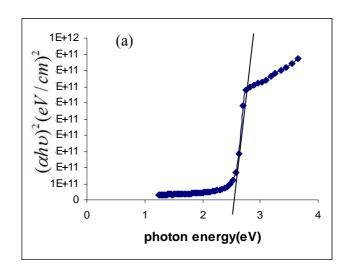
(eV) : $h\upsilon$

 $.(eV) \hspace{3.1in} \vdots \hspace{3.1in} E_g$

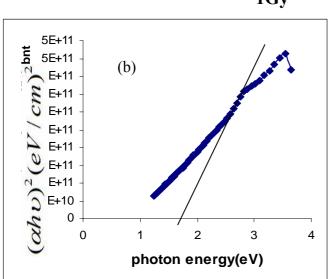
. (1/3)

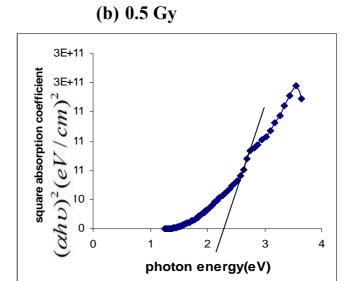
(α hυ)²





(a) ZnO 1Gy





 $(\alpha h \upsilon)^2$

:8

(a) ZnO 10h

 $(\alpha \, h \upsilon)^2$:9 (b) 4h

ZnO :3

96

 Dose (Gy)
 Band gap energy Eg (eV)

 0
 3.25

 0.5
 2.51

 1
 2.6

 2
 2.5

ZnO :4

Neutrons (hours)	Band gap energy Eg (eV)		
2	1.92		
4	2.3		
8	1.5		
10	1.7		

(4) (3)

Electrical Properties

(ZnO)

 $(8.79-12.56) \times 10^3 \Omega.cm$

 $\Omega.\text{cm}$

.0.236 x 10⁻³

(ZnO) (101) (002) (100)

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